

ABSTRACT

A manufacturing method for exposure apparatuses is provided in which a reticle R1 held on a reticle stage system RST is illuminated by exposure light from an exposure light source 16 via the illumination systems IL1 and IL2. In a first manufacturing line, a main body module composed of a frame caster 2, a main body support section 3, and a main body column 5 is assembled, and an illumination system and the projection optical system PL are mounted on this main body module. Then a stage module, which is assembled and adjusted using another main body module in a second manufacturing line, is mounted on the main body module of the first manufacturing line. Therefore exposure apparatuses can be efficiently manufactured without using dedicated large scale adjustment jigs.